

反应堆工程

U-10Mo/Al-Si固体扩散行为

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摘要 采用扩散偶方法研究U-10Mo合金与Al- x Si($x=0, 1, 2, 5, 7, 9$, 质量分数)合金的固体扩散行为。实验在真空热压炉中完成, 退火温度为555、570、580、590和595 °C, 时间为5~10 h。实验结果表明: 退火条件对扩散行为有显著影响, 580 °C是U-10Mo/Al-xSi扩散行为的重要分界点; 当温度低于580 °C热压退火处理时, 扩散层厚度随Si含量的增加先急剧减小然后缓慢增大; 当温度高于580 °C时, 扩散层的厚度随Si含量的增加而增加。Si含量较高($\geq 2\%$)的扩散偶扩散层厚度比低Si含量的小, 扩散层呈3层结构, 靠近Al-Si侧出现贫Si区。成分分析显示: Si含量较高的扩散偶, 靠近U-Mo侧的扩散薄层中出现Si的富集, 其成分为 $(U, Mo)(Al, Si)_x$ ($x \leq 3$); 靠近Al-Si合金侧的扩散层成分为 $(U, Mo)(Al, Si)_x$ ($x > 3$)。

关键词 [U-Mo合金](#) [Al-Si合金](#) [扩散偶](#) [扩散层](#)

分类号

Diffusion Behavior on U-10Mo/Al-Si Alloys

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Abstract The diffusion behavior between U-10Mo and Al-Si alloys was studied with diffusion-couple method. The couple was annealed in a high vacuum heat-pressure furnace at 555, 570, 580, 590 and 595 °C, respectively for 5-10 h. Annealing conditions have a significant effect on interaction-layer thickness. When temperature is lower than 580 °C with pressuring, the thickness suddenly decreases then slowly increases with the Si content increasing; however, when temperature is higher than 580 °C the thickness increases with the Si content increasing. Interaction layer with higher Si content which thickness is lower than that with lower Si content is composed of three layers. Si-rich layer with the composition of $(U, Mo)(Al, Si)_x$ ($x \leq 3$) closes to U-10Mo side, Si-poor layer with the composition of $(U, Mo)(Al, Si)_x$ ($x > 3$) closes to Al-Si side.

Key words [U-10Mo alloy](#) [Al-Si alloy](#) [diffusion-couple](#) [interaction layer](#)

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